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(71) Applicant (for all designated States except US): **KONINKLIJKE PHILIPS ELECTRONICS N.V.** [NL/NL];
Groenewoudseweg 1, NL-5621 BA Eindhoven (NL).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **VAN BEEK, Jozef, T., M.** [NL/NL]; c/o Prof. Holstlaan 6, NL-5656 AA Eindhoven (NL). **ULENAERS, Mathieu, J., E.** [BE/BE]; c/o Prof. Holstlaan 6, NL-5656 AA Eindhoven (NL).

(74) Agent: **ELEVELD, Koop, J.**; Prof. Holstlaan 6, NL-5656 AA Eindhoven (NL).

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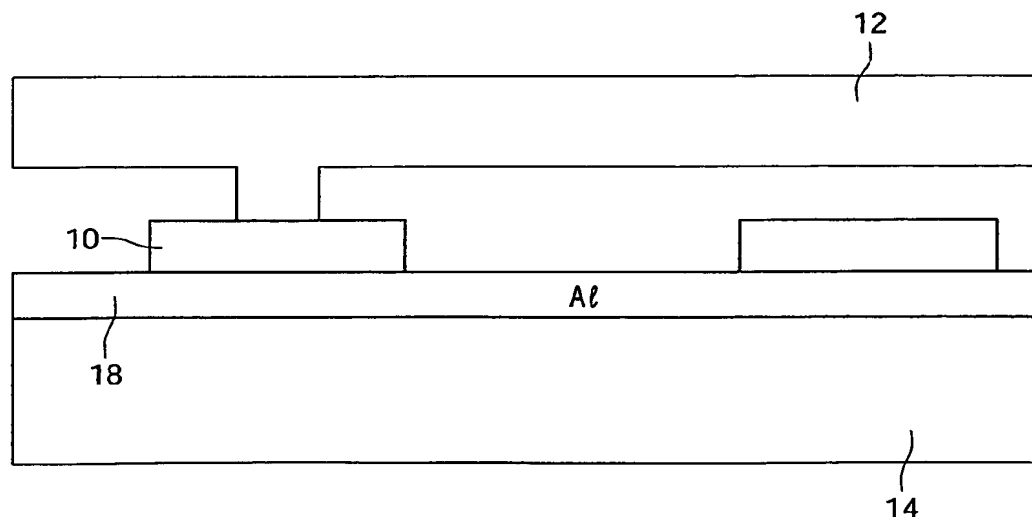
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(54) Title: A METHOD OF MANUFACTURING AN ELECTRONIC DEVICE AND ELECTRONIC DEVICE



(57) Abstract: 16 ABSTRACT: A method of manufacturing a micro-electromechanical systems (MEMS) device, comprising providing a base layer (10) and a mechanical layer (12) on a substrate (14), providing a sacrificial layer (16) between the base layer (10) and the mechanical layer (12), providing an etch stop layer (18) between the sacrificial layer (16) and the substrate (14), and removing the sacrificial layer (16) by means of dry chemical etching, wherein the dry chemical etching is performed using a fluorine-containing plasma, and the etch stop layer (18) comprises a substantially non-conducting, fluorine chemistry inert material, such as HfO₂, ZrO₂, Al₂O₃ or TiO₂.

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